

35781 U.S. PTO  
10/026973

12/27/01

PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10026973	12/27/2001	430	5	1756	Rosasco

**\*\*APPLICANTS:** Hattori Takashi; Gotoh Yasuko; Satoh Hidetoshi; Tanaka Toshihiko;  
Shiraishi Hiroshi;

**\*\*CONTINUING DATA VERIFIED:**

**\*\* FOREIGN APPLICATIONS VERIFIED:**

JAPAN 2000-401154 12/28/2000

PG-PUB DO NOT PUBLISH ☐

RESCIND ☐

Foreign priority claimed

☒ yes ☐ no

35 USC 119 conditions met

☒ yes ☐ no

Verified and Acknowledged Examiners's initials

ATTORNEY DOCKET NO

T&A-109

**TITLE :** Photomask, the manufacturing method, a patterning method, and a semiconductor device manufacturing method

U.S. DEPT. OF COMM./PAT & TM-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED		
		Assistant Examiner	Total Claims	
			Print Claim for O.G.	
ISSUE FEE		Primary Examiner	DRAWING	
Amount Due	Date Paid		Sheets Drawn	Print Fig.
			Application Examiner	
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE		
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